

EE128 Homework Set 4

If not specified the temperature for all problems is 300K and the substrate is Silicon, with an Oxide of SiO₂.

Question 1:

An n⁺-polysilicon-gate n-channel MOS transistor is made on a p-type Si substrate with $N_a=5 \times 10^{15} \text{ cm}^{-3}$. The SiO₂ thickness is 100 Å in the gate region, and the effective interface charge is $Q_i=4 \times 10^{10} \text{ qC/cm}^2$. Assume 300K.

Calculate W_M , V_{FB} , and V_T .

Question 2:

An n-channel MOSFET with a 400\AA gate oxide has a V_T that is supposed to be 1Volt after coming back from ion implantation. After measurement, it turns out that $V_T=3\text{Volts}$. What happened?

Question 3:

Plot I_D vs. V_D (Excel like program) for several values of V_G for the following p-MOS transistor.

Gate:n+poly Si, $N_d=10^{16}\text{cm}^{-3}$, $Q_i=5\times 10^{10}\text{qC/cm}^2$, $t_{ox}=0.01\times 10^{-4}\text{cm}$, $\mu_p=200\text{cm}^2/\text{V-s}$, and $Z=10L$. Assume I_D is constant after pinch off.

Question 4:

A typical figure of merit for high frequency operation is $f_c = g_m / 2\pi C_G L Z$ (cut off frequency), where the gate capacitance is C_i over much of the voltage range. Express f_c above pinch-off in terms of material parameters and device dimensions, and calculate f_c for the MOSFET in problem 3, with $L = 1\mu\text{m}$.

Question 5:

A given MOSFET has n^+ ($N_d = 10^{20}\text{cm}^{-3}$) S/D contacts separated by 1mm ($L = 1 \times 10^{-4}\text{cm}$). The substrate doping is $N_a = 10^{16}\text{cm}^{-3}$. Assume that the source and body are grounded. At what V_D will the two depletion widths of the two diodes meet?

Question 6:

An n^+ -polysilicon-gate line is passing over a field oxide region. What thickness of oxide do you need to have a $V_T = > 10\text{V}$, if the n -channel parasitic MOS transistor is made on a p -type Si substrate with $N_a = 5 \times 10^{15}\text{cm}^{-3}$, and the effective interface charge is $Q_i = 4 \times 10^{10}\text{qC/cm}^2$.

Question 7:

The figure below shows the measured CV data of a MIS capacitor on p-type <100> silicon substrate with an aluminum gate ($\phi_{ms} = -.6\text{eV} - U_T \times \ln(N_A/n_i)$) (The Insulator is SiO_2 .) Extract d , (t_{ox}) N_A , V_T , and fixed oxide charge. (Room temperature conditions apply.) Hint, you do not have to scale the measured data by the area.

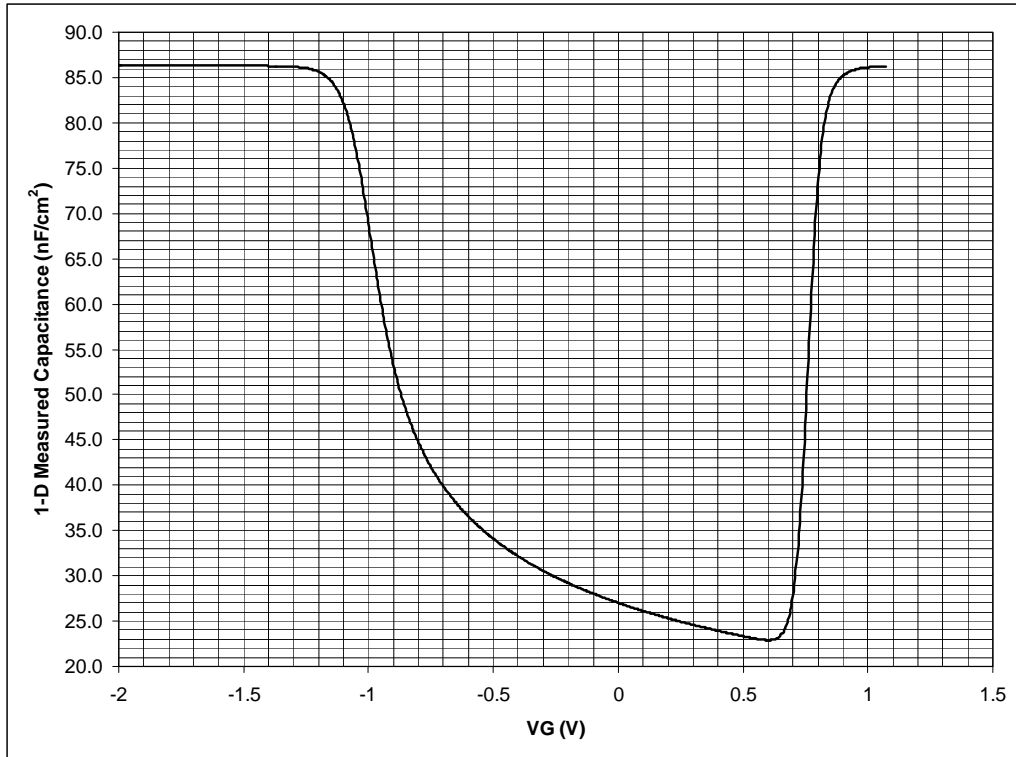


Figure 1: Measured 1-D CV plot of MIS capacitor.

Question 8:

Estimate V_T from the following graph ($V_{DS}=V_{GS}$):

